

Form PTO-1449 U.S. Department of Commerce (Rev. 8-83) Patent and Trademark Office		Atty. Docket No.: 0756-1630		Serial No. 08/799,506	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicant: Shunpei YAMAZAKI, et al.			
		Filing Date: February 12, 1997		Group: 2822	


U.S. PATENT DOCUMENTS							
Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)	
MW	5,581,092	12/03/96	Takemura				
MW	5,595,638	01/21/97	KONUMA ET AL.				
MW	5,608,232	03/04/97	YAMAZAKI ET AL.				
MW	5,608,251	03/04/97	KONUMA ET AL.				
MW	5,620,095	04/15/97	KONUMA ET AL.				
MW	5,639,698	06/17/97	YAMAZAKI ET AL.				
MW	4,151,058	04/24/79	KAPLAN				
MW	4,226,898	10/07/80	OVSHINSKY				
MW	4,313,783	02/02/82	DAVIES ET AL.				
MW	4,322,253	03/30/82	PANKOVE				

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
MW	01-128446	05/22/89	JAPAN		ABST.		
MW	02-257619	10/18/90	JAPAN		ABST.		
MW	04-206532	07/28/92	JAPAN		ABST.		
MW	05-182923	07/23/93	JAPAN		ABST.		
MW	57-194518	11/30/82	JAPAN		ABST.		
MW	64-076737	03/22/89	JAPAN		ABST.		
MW	0211634	02/25/87	EP		FULL		

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)	
MW	Kawashi, et al., "LARGE-AREA DOPING PROCESS FOR FABRICATION OF poly-Si THIN FILM TRANSISTORS USING BUCKET ION SOURCE AND XeCl EXCIMER LASER ANNEALING," Japanese Journal of Applied Physics, No. 12, December, pp. L2370-L2372.
MW	Sameshima, et al., "XeCl EXCIMER LASER ANNEALING USED TO FABRICATE POLY-Si TFT's," Japanese Journal of Applied Physics, Vol. 28, No. 10, October 1989, pp. 1789-1793.
MW	Wagner, et al., "FORMATION OF p-n JUNCTIONS & SILICIDES IN SILICON USING A HIGH PERFORMANCE LASER BEAM HOMOGENIZATION SYSTEM," Applied Surface Science 43 (1989) 260-263, North Holland.
MW	Sera, et al., "HIGH-PERFORMANCE TFT'S FABRICATED BY XeCl EXCIMER LASER ANNEALING OF HYDROGENATED AMORPHOUS-SILICON FILM," IEEE Transactions on Electron Devices, Col. 36, No. 12, December 1989, pp. 2868-2872.
Examiner <u>MWilezowski</u> Date Considered <u>9/2000</u>	

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U.S. PATENT DOCUMENTS							
Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)	
MW	4,370,175	01/25/83	LEVATTER				
MW	4,388,145	06/14/83	HAWKINS ET AL.				
MW	4,402,762	09/06/83	JOHN ET AL.				
MW	4,405,435	09/20/83	TATEISHI ET AL.				
MW	4,498,416	02/12/85	BOUCHAIB				
MW	4,503,807	03/12/85	NAKAYAMA ET AL.				
MW	4,523,370	06/18/85	SULLIVAN ET AL.				
MW	4,552,595	11/12/85	HOGA				
MW	4,557,036	12/10/85	KYURAGI ET AL.				
MW	4,567,061	01/28/86	HAYASHI ET AL.				

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation Yes No		
MW	60-042817	03/07/85	JAPAN				X
MW	63-160336	07/04/88	JAPAN			ABST.	
MW	01-179410	07/17/89	JAPAN			ABST.	
MW	03-024717	02/01/91	JAPAN			ABST.	
MW	62-104117	05/14/87	JAPAN			FULL	
MW	02-239615	09/21/90	JAPAN			FULL	
MW	02-081424	03/22/90	JAPAN			ABST.	


OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)	
MW	Kuwano, et al., "PHOTOVOLTAIC BEHAVIOR OF AMORPHOUS Si:H AND Si:F:H SOLAR CELLS," Conference Record, 15 th IEEE Photovoltaic Specialists Conf., Kissimmee, Florida, USA, May 12-15, 1981, Published August 1981.

Examiner <i>MWitczewski</i>	Date Considered <i>9/2000</i>
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<i>MW</i> <i>MW</i> <i>MW</i> <i>MW</i> <i>MW</i> <i>MW</i> <i>MW</i> <i>MW</i> <i>MW</i>		4,576,851 4,582,720 4,590,091 4,590,091 4,592,306 4,592,799 4,595,601 4,609,407 4,640,223 4,694,143	03/18/86 04/15/86 05/20/86 05/20/86 06/03/86 06/03/86 06/17/86 09/02/86 02/03/87 09/15/87	IWAMATSU YAMAZAKI KAWAMURA ROGERS ET AL. GALLEGO HAYAFUJI HORIOKA ET AL. MASAO ET AL. DOZIER NISHIMURA ET AL.	<div style="font-size: 4em; line-height: 1;">X</div>		
FOREIGN PATENT DOCUMENTS							
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Examiner	<i>MWileczewski</i>			Date Considered	<i>9/00</i>		
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MW	4,698,486	10/06/87	SHEETS				
MW	4,699,863	10/13/87	SAWATARI ET AL.				
MW	4,719,123	01/12/88	HAKU ET AL.				
MW	4,843,022	06/27/89	YAMAZAKI				
MW	4,951,601	08/28/90	MAYDAN ET AL.				
MW	4,986,213	01/22/91	YAMAZAKI ET AL.				
MW	5,091,334	02/25/92	YAMAZAKI				
MW	5,141,058	08/25/92	HEPPNER				
MW	5,171,710	12/15/92	YAMAZAKI				
MW	5,296,405	03/22/94	YAMAZAKI ET AL.				


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MW	5,314,839	05/24/94	MIZUTANI ET AL.				
MW	4,113,514	09/12/78	PANKOVE ET AL.				
MW	4,151,007	04/24/74	LEVINSTEIN ET AL.				
MW	4,331,709	05/25/82	RISCH ET AL.				
MW	4,398,343	08/16/83	TAMAZAKI				
MW	4,482,395	11/13/84	HIRAMOTO				
MW	5,424,244	06/13/95	ZHANG ET AL.				
MW	5,840,600	11/24/98	YAMAZAKI ET AL.				
MW	5,879,969	03/09/99	YAMAZAKI ET AL.				
MW	5,294,811	03/15/94	AOYAMA ET AL.				

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